



Attorney's Docket No. 42390P10606

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

#81C  
5/10/3  
Sunder

In re Application of:

Qing Ma, Peng Cheng

Serial No. 09/894,334

Filed: June 27, 2001

For: SACRIFICIAL LAYER TECHNIQUE  
TO MAKE GAPS IN MEMS  
APPLICATIONS

Examiner: Coleman, William D.

Art Unit: 2823

Confirmation No.: 6477

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PRELIMINARY AMENDMENT

Box Amendment  
Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

In response to the Office Action mailed January 24, 2003, and the Advisory Action mailed April 15, 2003, please amend the above-identified application as follows, and consider the Request for Continued Examination (RCE) filed herewith, and consider the following remarks.

IN THE CLAIMS

Please cancel Claims 6 and 13 without prejudice or disclaimer.

Please amend the claims as follows:

- C
1. (Twice Amended) A method comprising:  
over an area of a substrate, forming a plurality of three dimensional first structures;  
following forming the first structures, conformally introducing a sacrificial material over the area of the substrate;  
introducing a second structural material over the sacrificial material;  
exposing a portion of the sacrificial material;